

AMENDMENTS TO THE CLAIMS

Claims 1-11 (canceled)

Claim 12 (currently amended): A substrate processing method ~~for processing a substrate to be processed, by supplying processing gas and solvent vapor to the substrate accommodated in a processing container, the method comprising the steps of:~~

~~researching on a pressure of the solvent vapor in a condition before the solvent vapor is supplied into the processing container;~~

~~supplying the solvent vapor into the processing container on the basis of the pressure of the solvent vapor;~~

placing a substrate in a processing container;

supplying a processing gas into the processing container to establish an atmosphere of a positive pressure in a processing container;

determining pressure of a solvent vapor in a solvent vapor generator;

comparing the pressure in the solvent vapor generator with pressure in the processing container supplied with the processing gas; and

supplying the solvent vapor from the solvent vapor generator into the processing container when the pressure in the solvent vapor generator is higher than the pressure in the processing container supplied with the processing gas.

Claim 13 (currently amended): A substrate processing method as claimed in Claim 12, wherein the ~~researching step for the pressure of the solvent vapor in the condition before being supplied into the processing container;~~ the step of determining the pressure in the solvent vapor generator is carried out by firstly measuring [[a]] temperature of the solvent vapor in the condition before being supplied into the processing container in the solvent vapor generator and secondly calculating the pressure ~~from the detected temperature~~ in the solvent vapor generator based on the measured temperature.

Claim 14 (currently amended): A substrate processing method as claimed in Claim 12, wherein ~~the researching step for the pressure of the solvent vapor in the condition before being supplied into the processing container~~ the step of determining the pressure in the solvent vapor generator is carried out by firstly measuring ~~[[a]] temperature of a liquid solvent that can generate the solvent vapor to be supplied into the processing container before vaporized in the solvent vapor generator~~ and secondly calculating the pressure ~~from the detected temperature in the solvent vapor generator~~ based on the measured temperature.

Claim 15 (canceled)

Claim 16 (currently amended): A substrate processing method for processing a substrate to be processed, by supplying processing gas and solvent vapor to the substrate accommodated in a processing container, the method comprising the steps of:

supplying the processing gas into the processing container to pressurize an interior of the processing container;

elevating a pressure of the solvent vapor before being supplied into the processing container higher than a pressure of the processing gas in the processing container; and

supplying the solvent vapor, whose pressure has been elevated higher than the pressure of the processing gas in the processing container, into the processing container.

Claim 17 (original): A substrate processing method as claimed in Claim 16, further comprising the step of controlling the pressure of the solvent vapor so as to be higher than a pressure of an atmosphere in the processing container, under condition that the pressure of the solvent vapor before being supplied into the processing container becomes higher than the pressure of the processing gas in the processing container.

Claim 18 (original): A substrate processing method as claimed in Claim 17, wherein the step of controlling the pressure of the solvent vapor so as to be higher than the pressure of the atmosphere in the processing container is carried, in a closed space where the solvent vapor before being supplied into the processing container is present, by releasing the closed space for a constant period to discharge the solvent vapor of a constant quantity from the closed space so that the pressure of the solvent vapor becomes less than a first pressure which is higher than the pressure of the processing gas in the processing container.

Claim 19-27 (canceled)